

Fig. 1

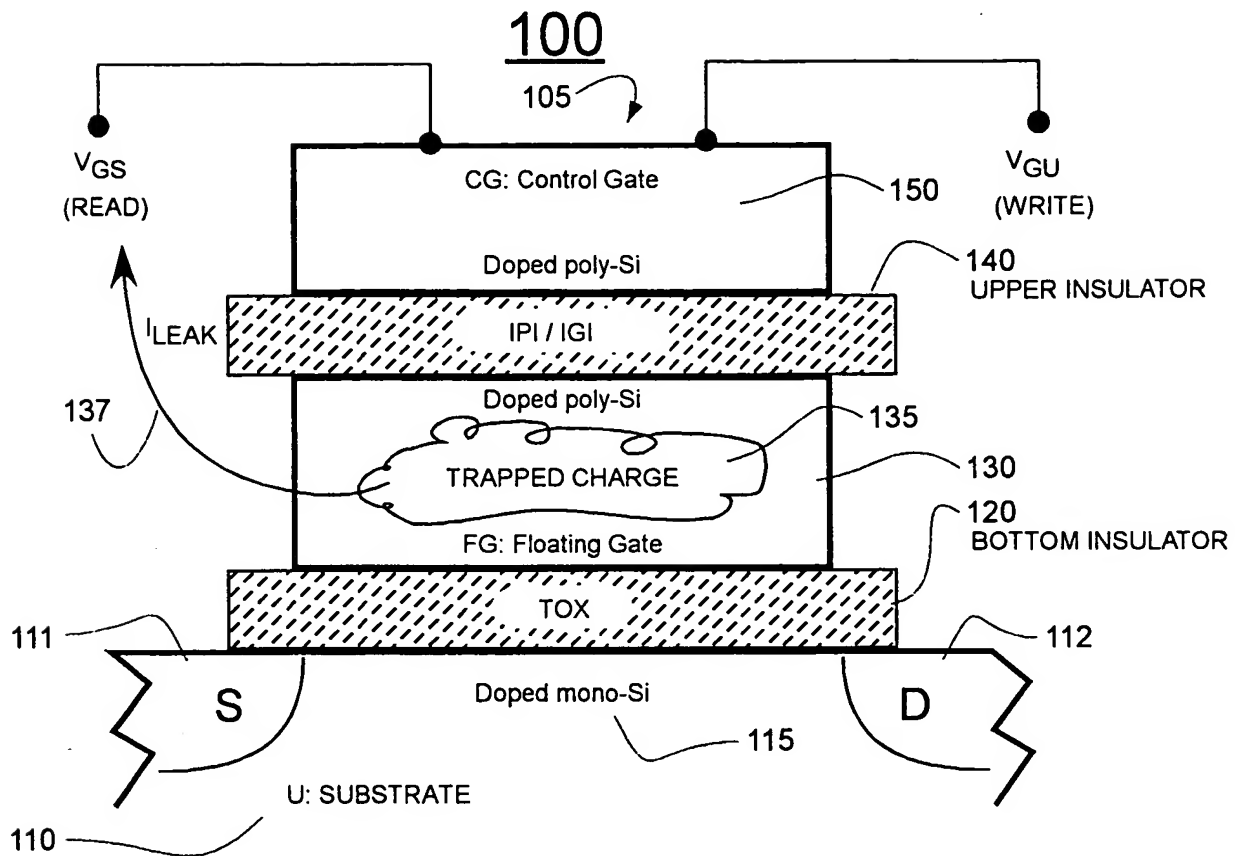


Fig. 2

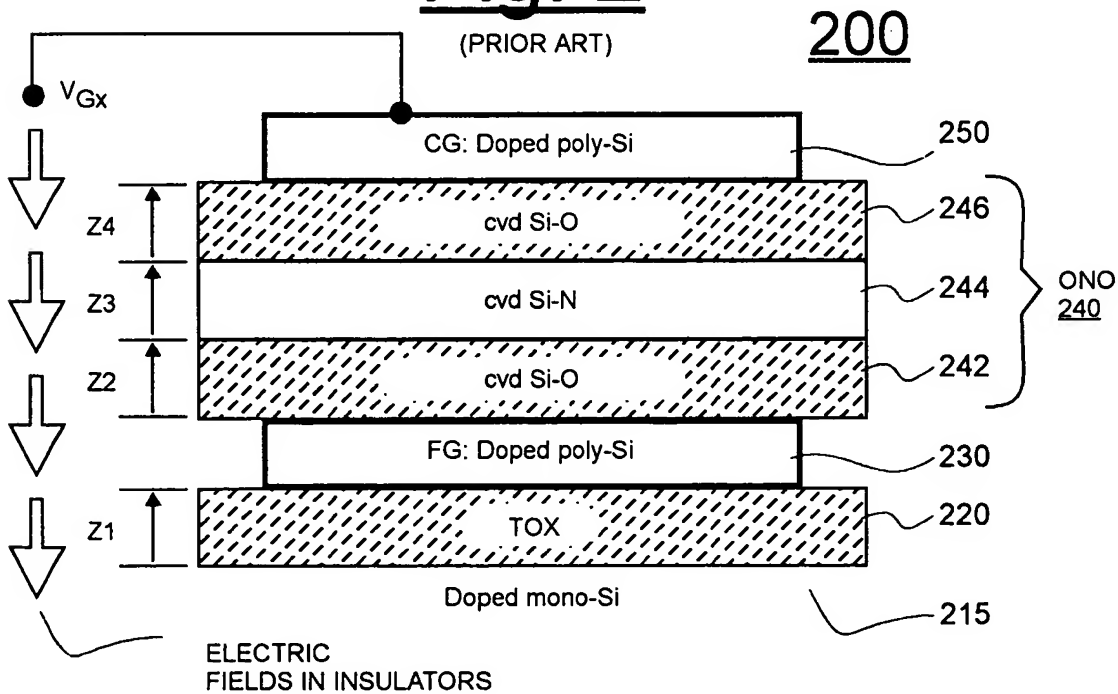


Fig. 3A

301 POLY-1 DEPOSITION

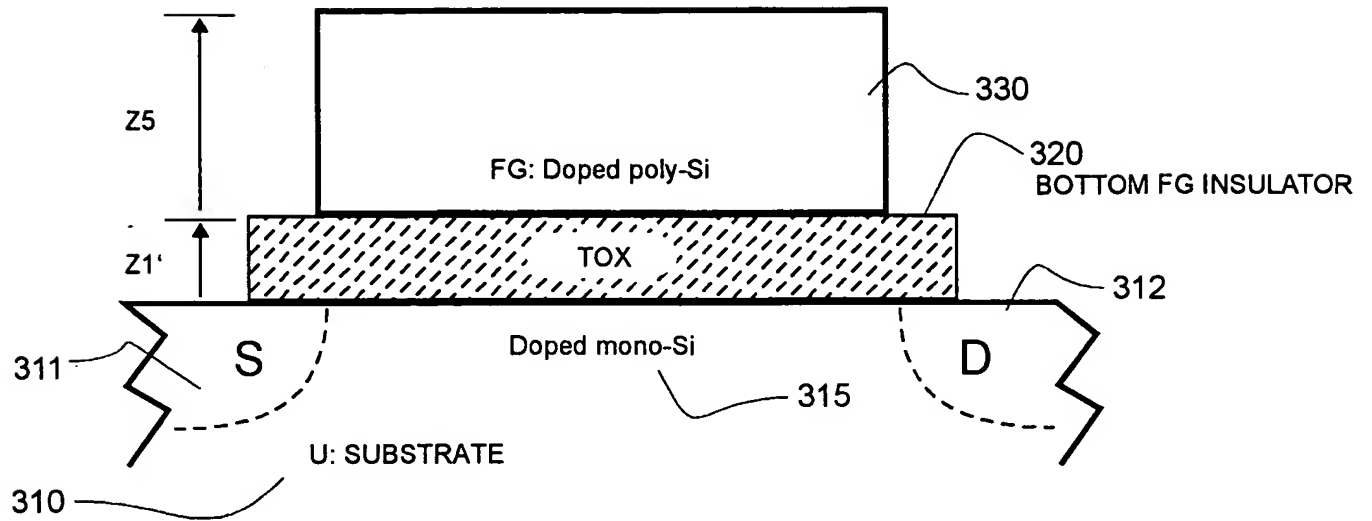


Fig. 3B

302 NITRIDATION

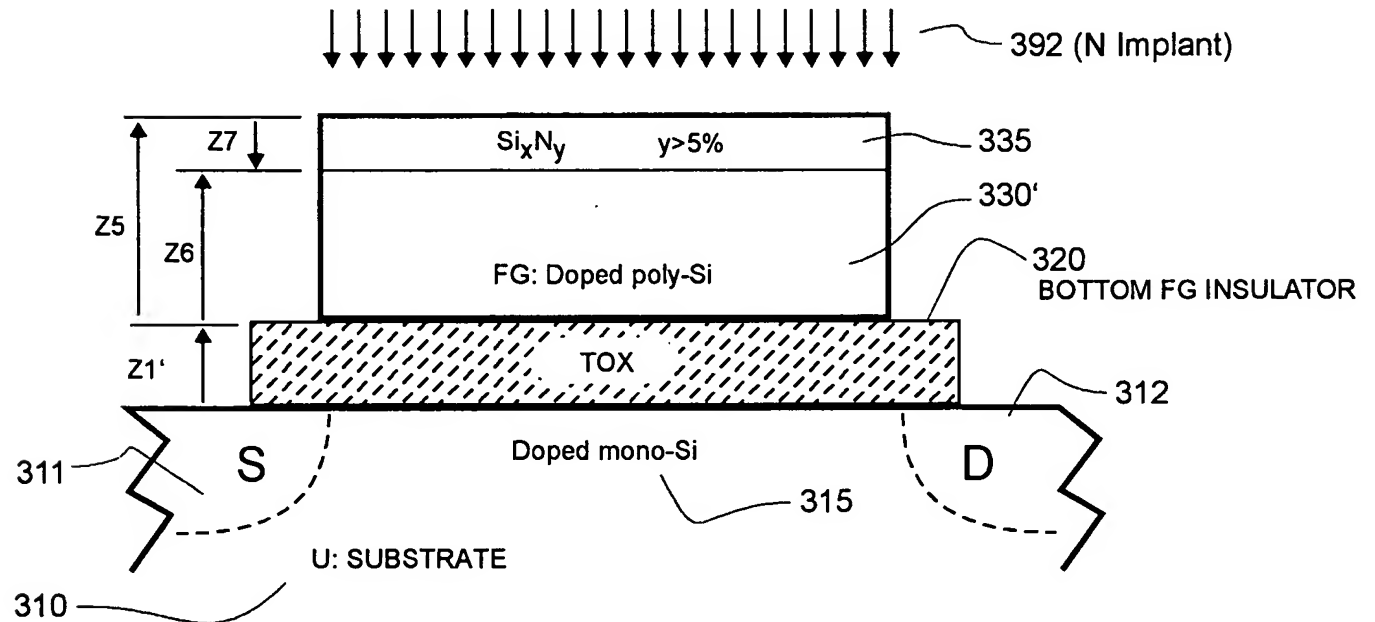


Fig. 3C

303 Atomic Layer Deposition of Intrinsic Si

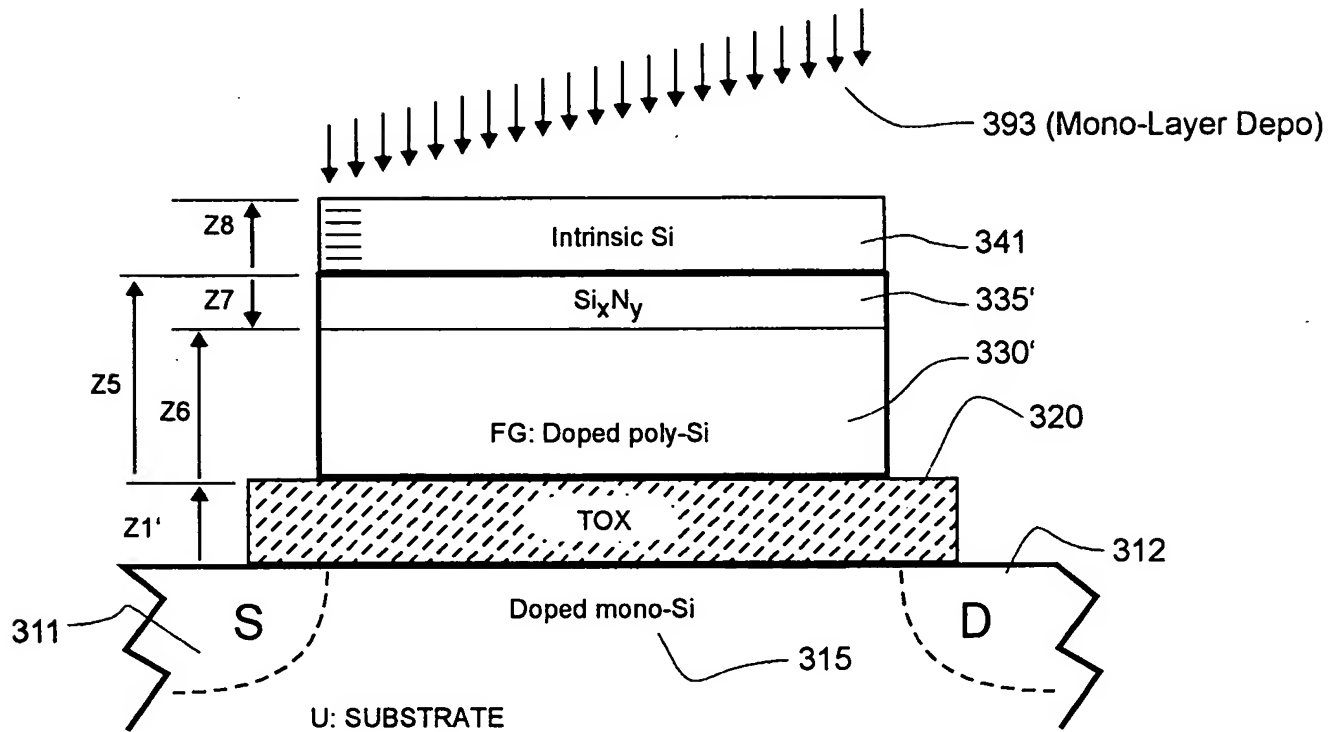


Fig. 3D

304 Begin Oxidation of Intrinsic Si

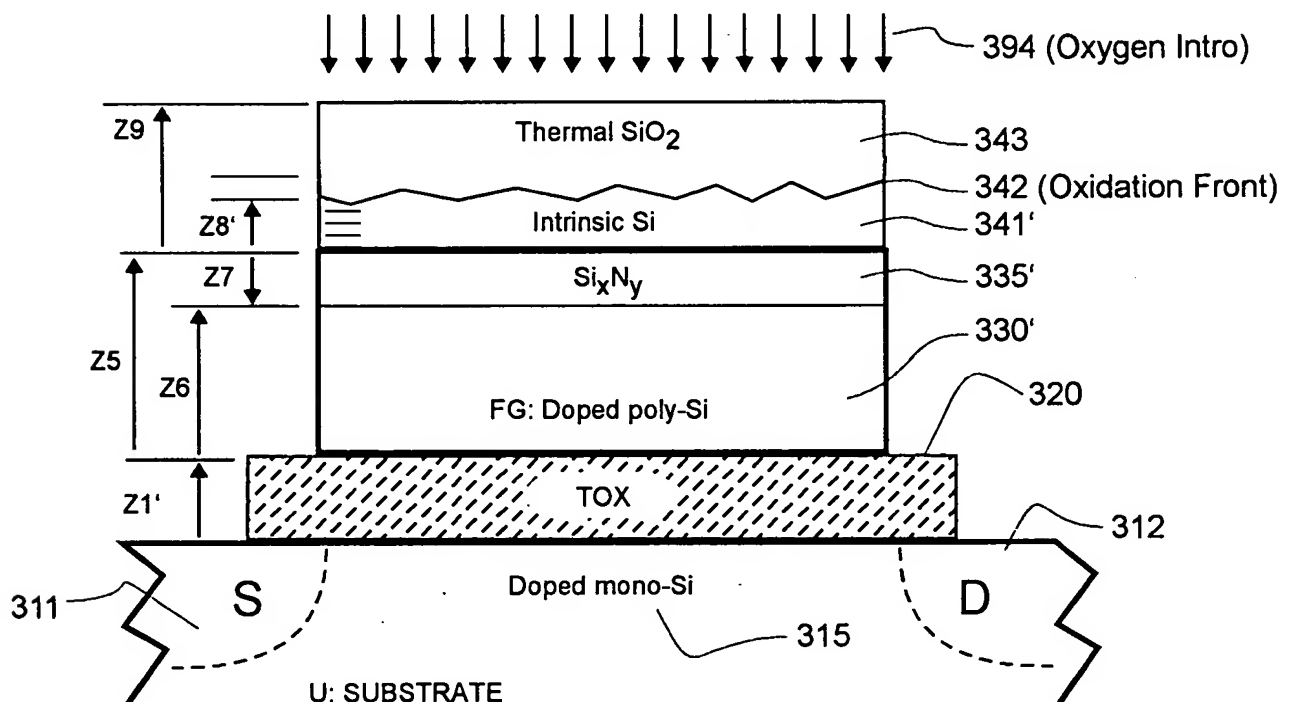


Fig. 3E

305

Continue Oxidation of Intrinsic Si

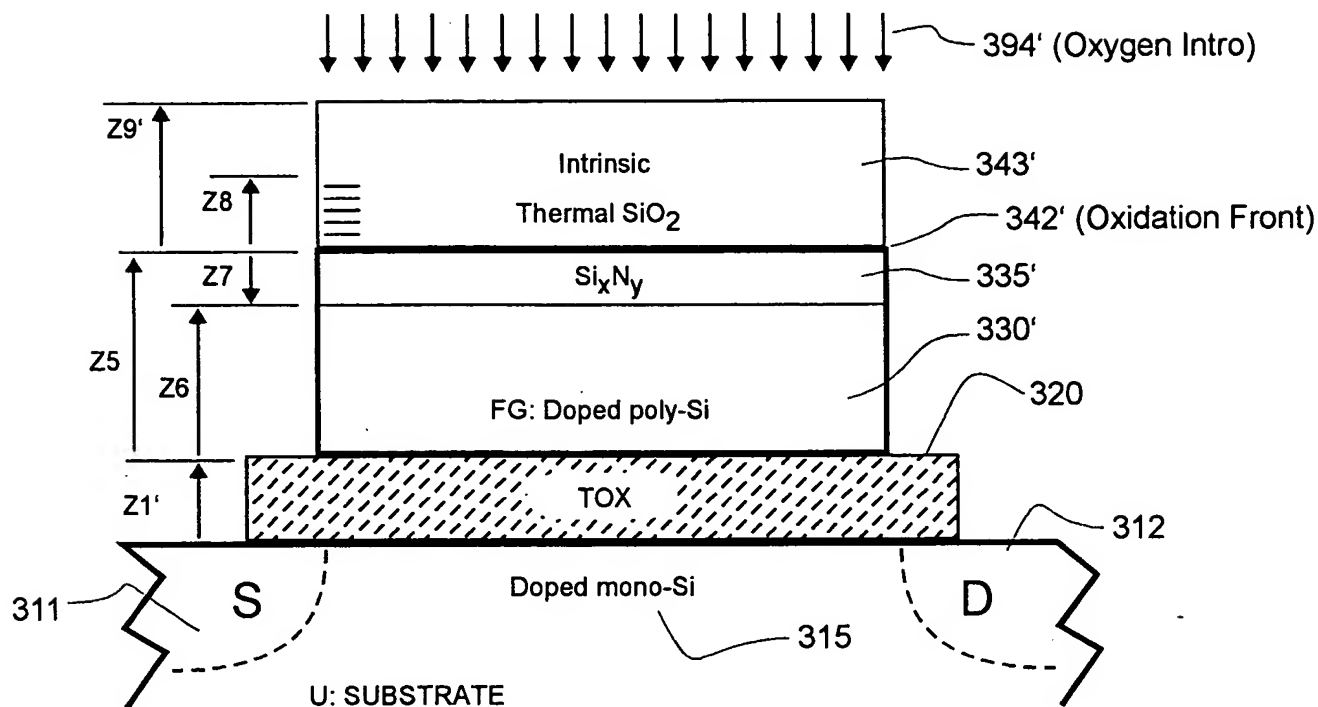


Fig. 3F

306

Drive Oxidation Into Nitride Stop

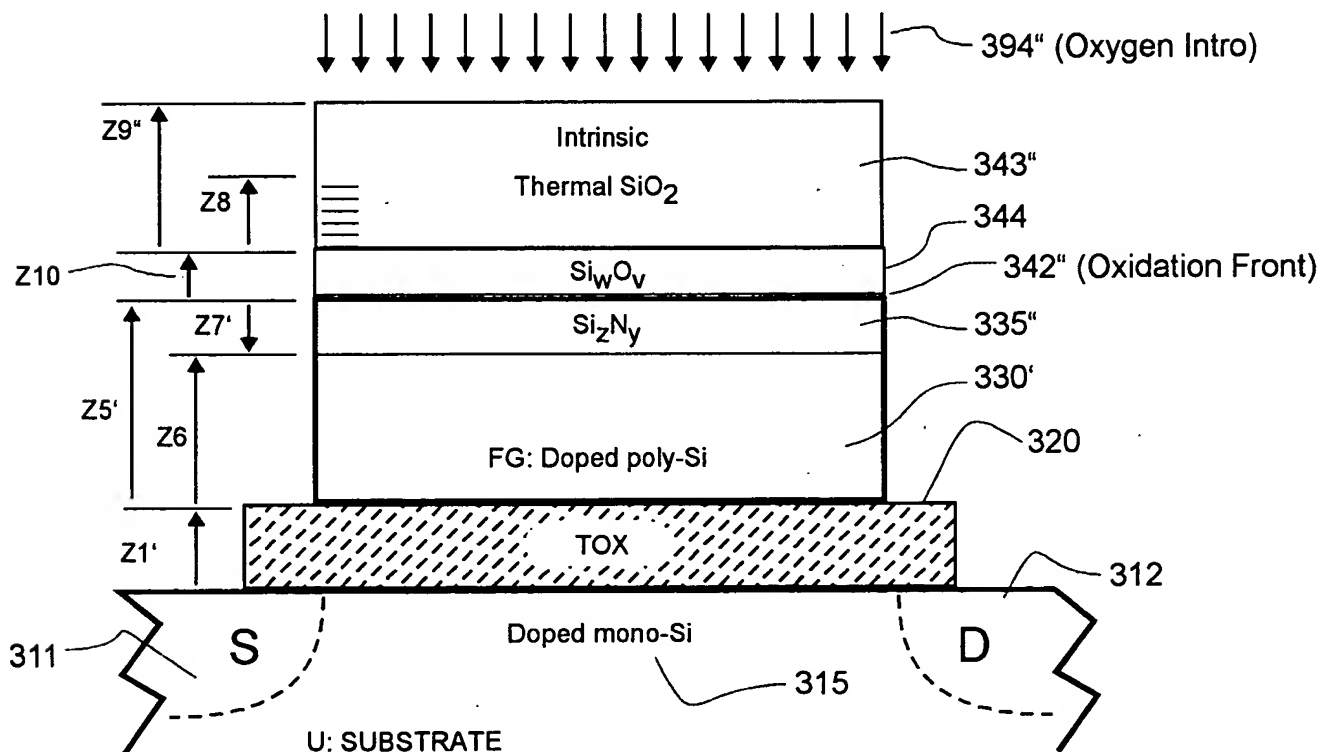


Fig. 3G

307

Deposit Middle SiN Layer

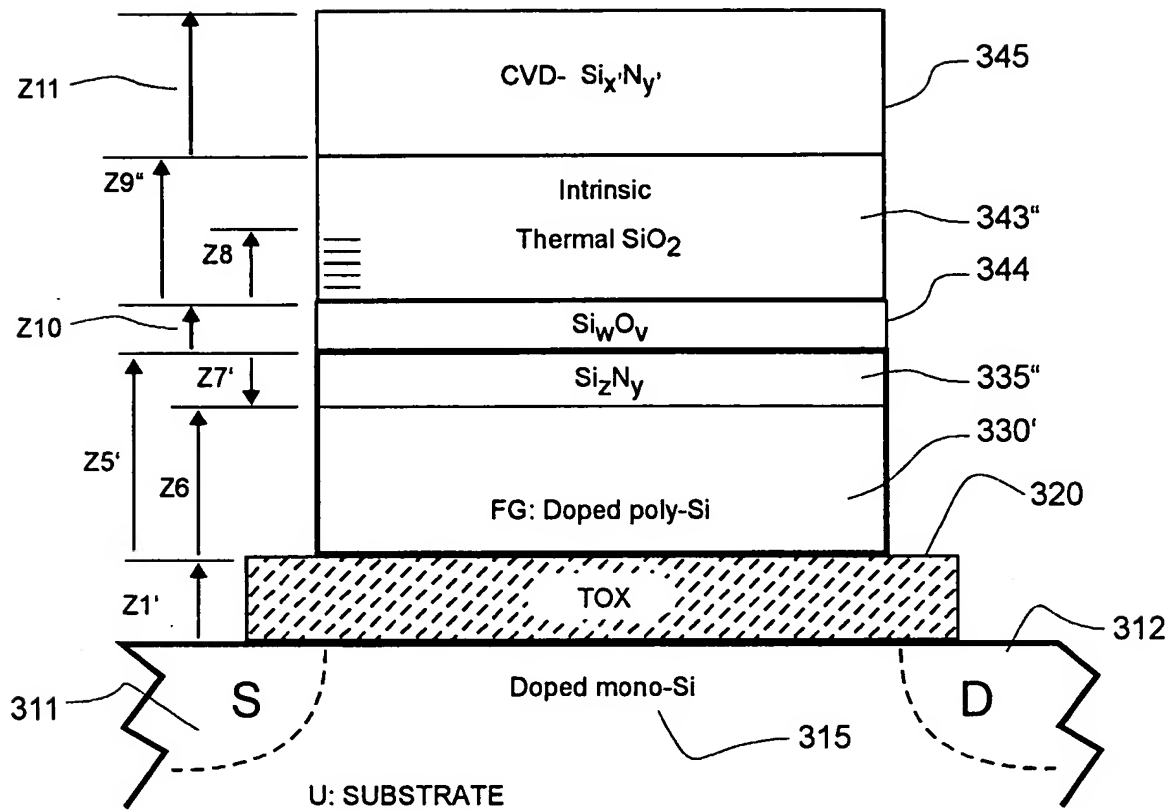


Fig. 3H

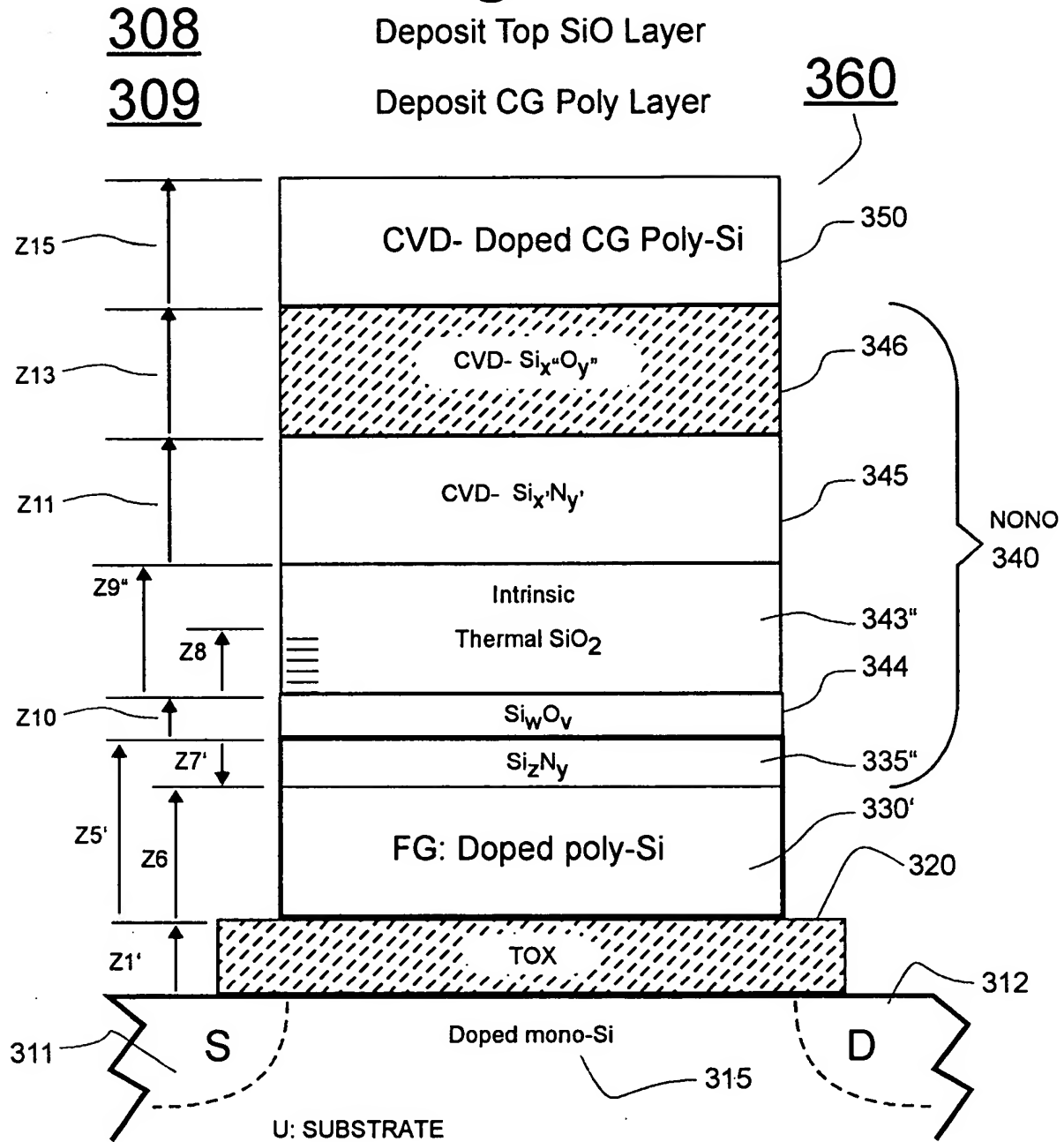


Fig. 4A

407 Atomic Layer Deposition of Intrinsic Si

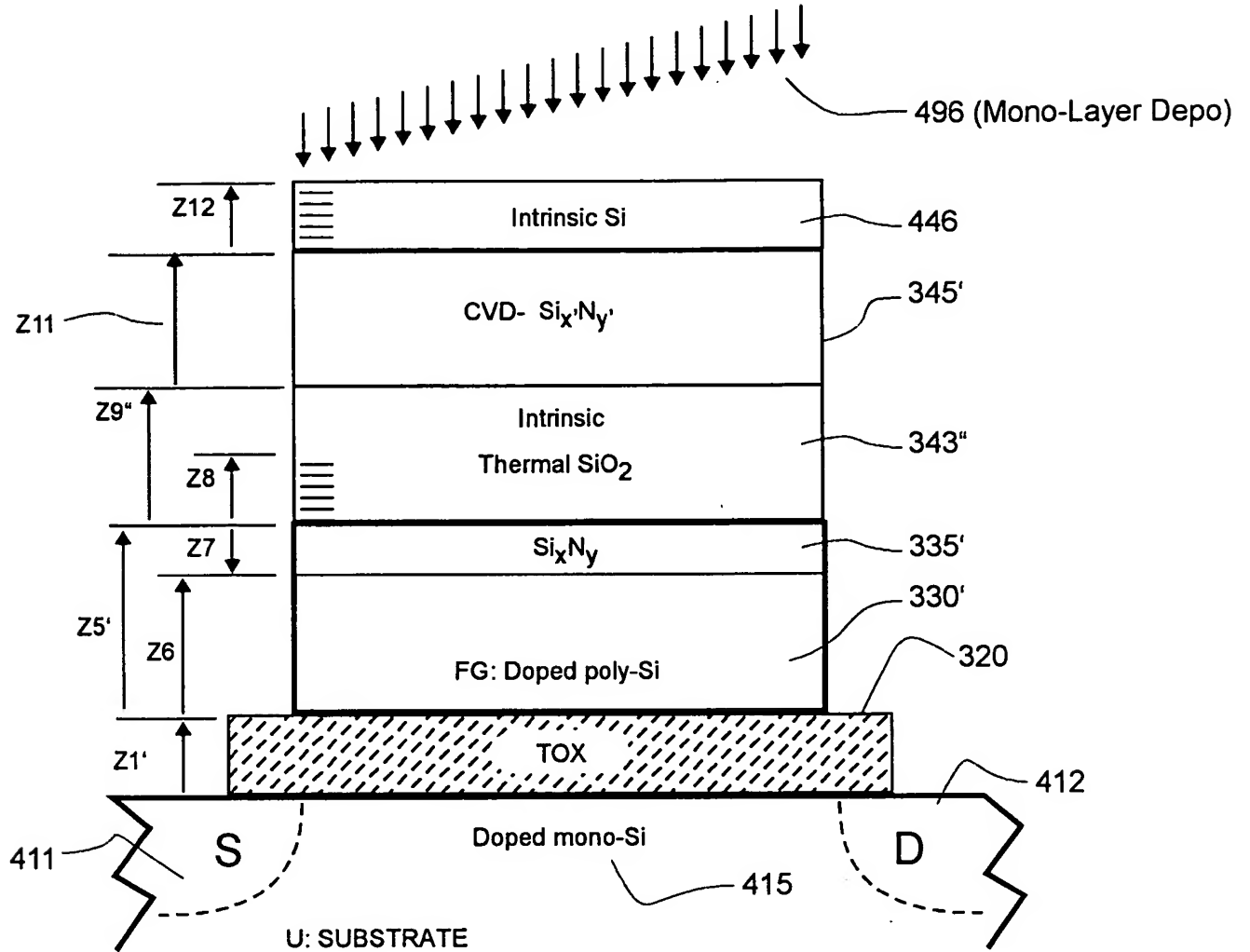


Fig. 4B

408 Begin Oxidation of Intrinsic Si

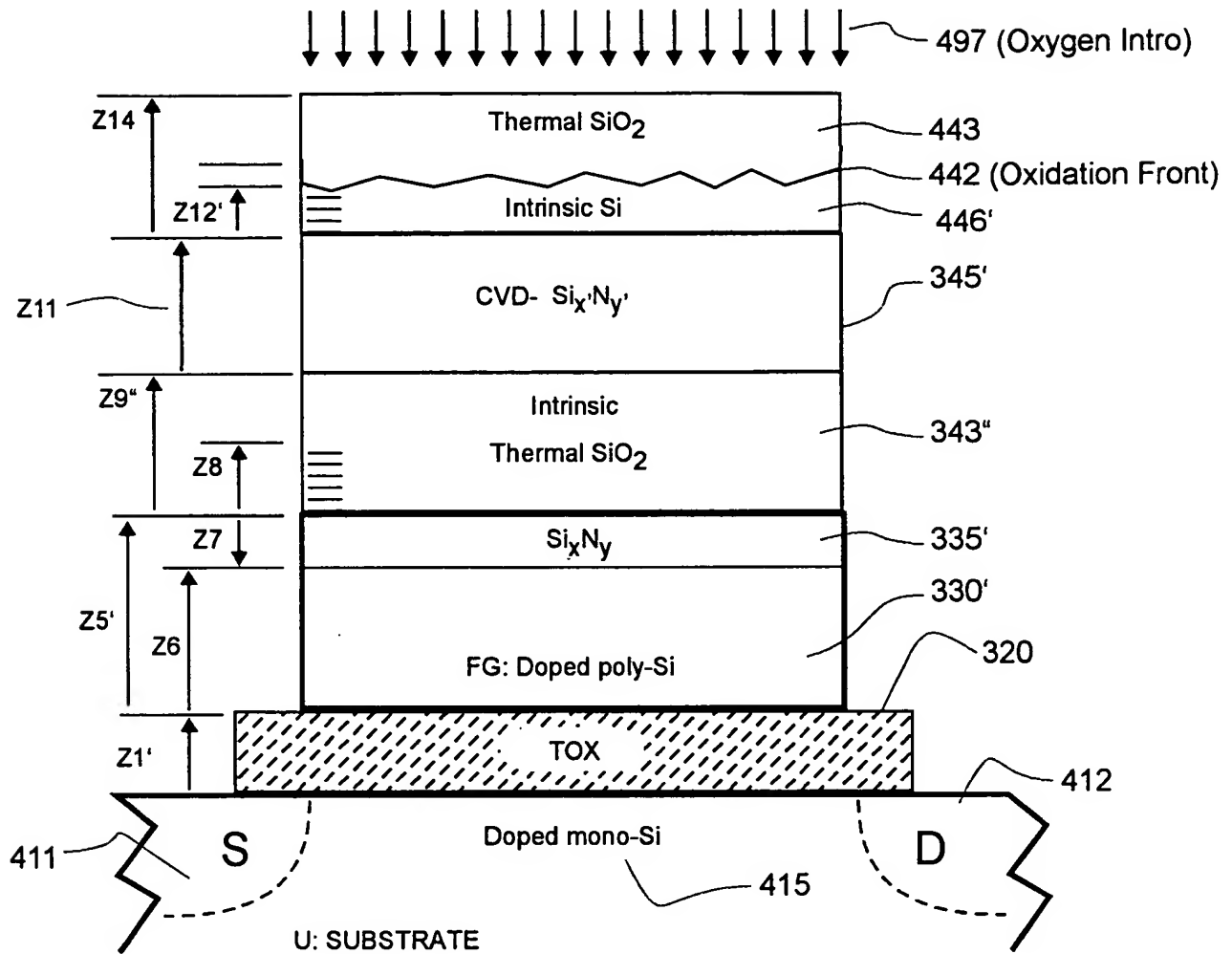


Fig. 4C

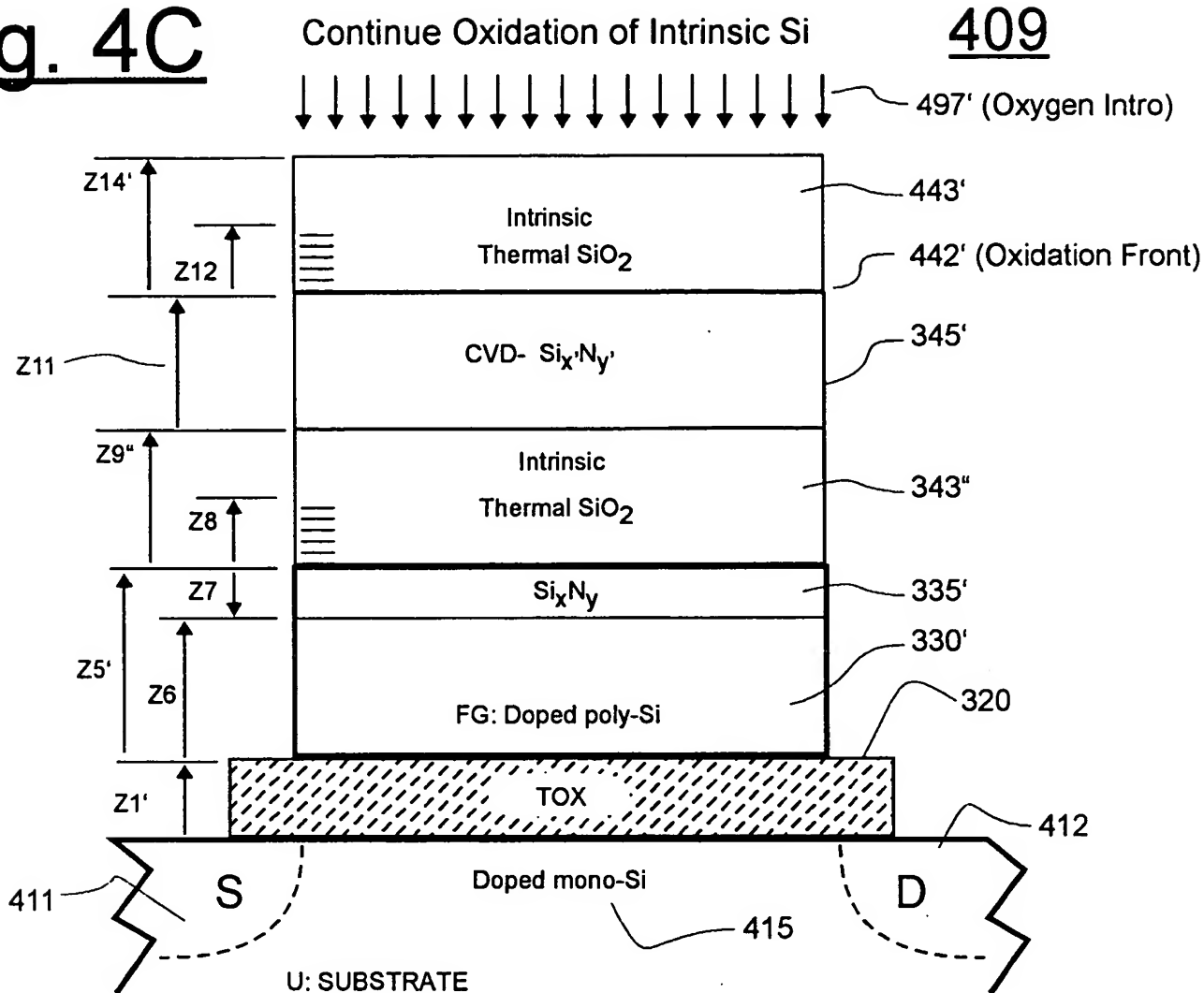


Fig. 4D

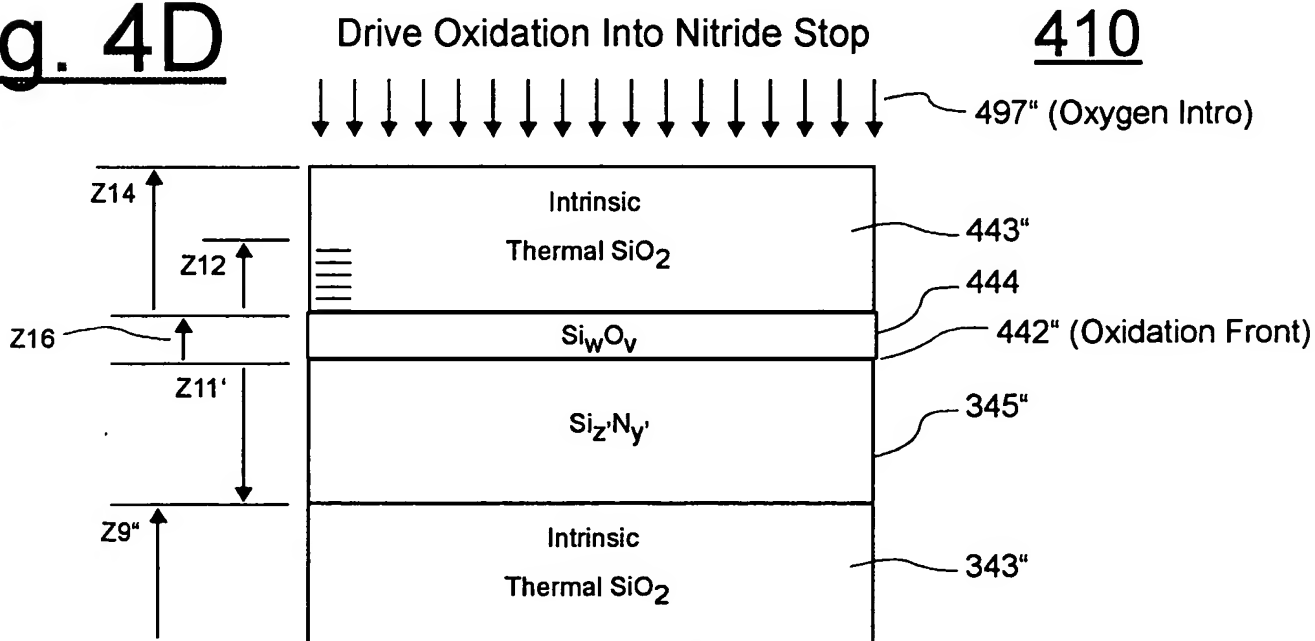


Fig. 4E

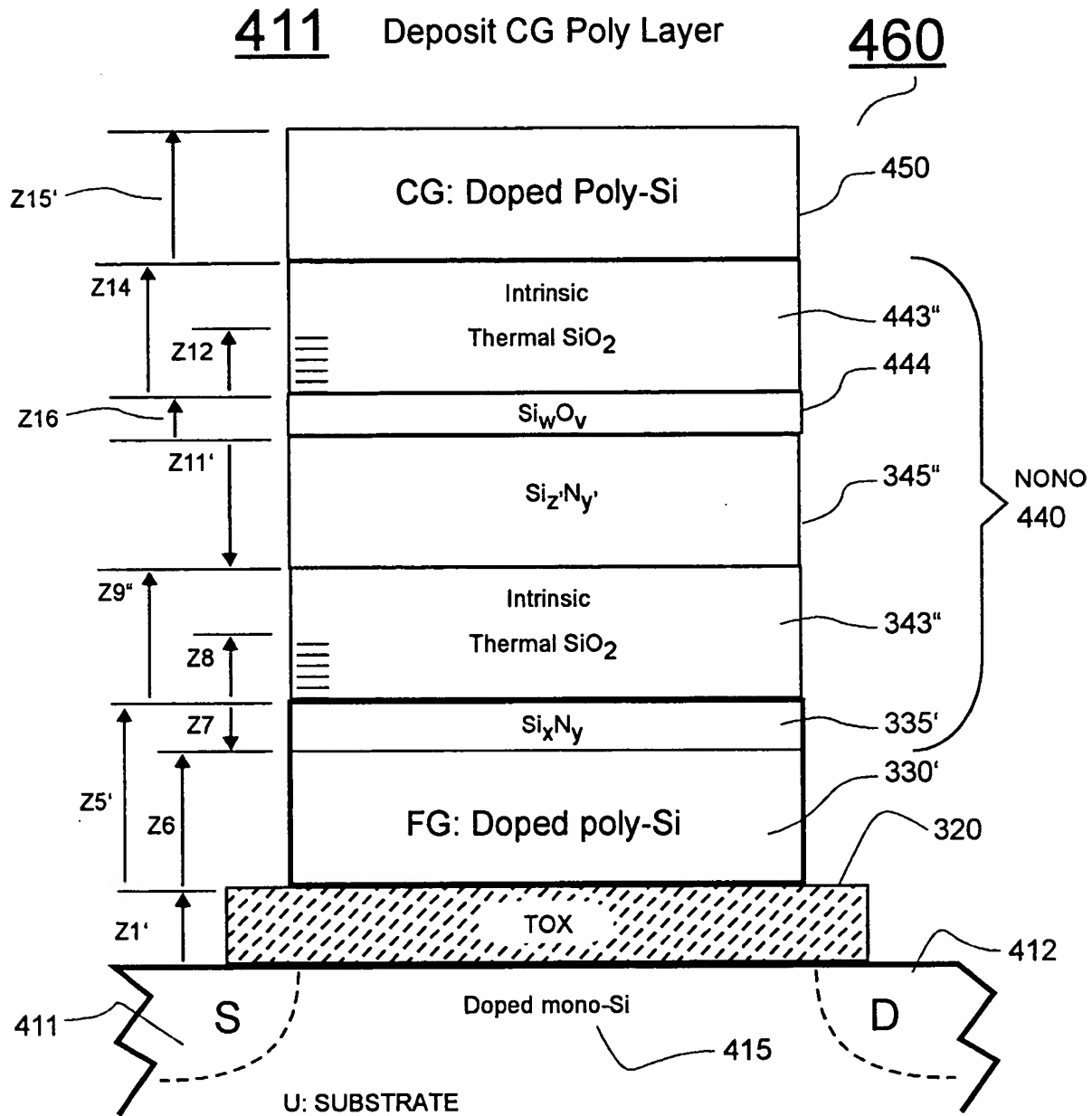


Fig. 4F

